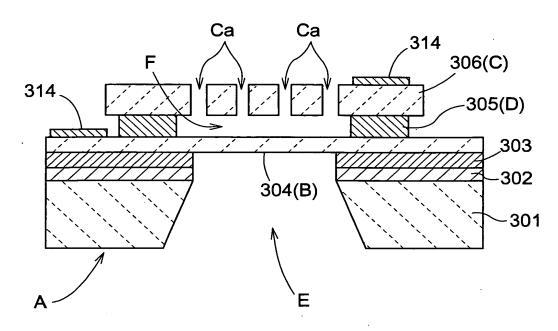
10/544120 Rec'd PCT/PTO 02 AUG 2005

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FIG.1



A: support substrate 301: monocrystal silicon substrate

B: diaphragm 302: silicon oxide film

C: back electrode 303: silicon nitride film

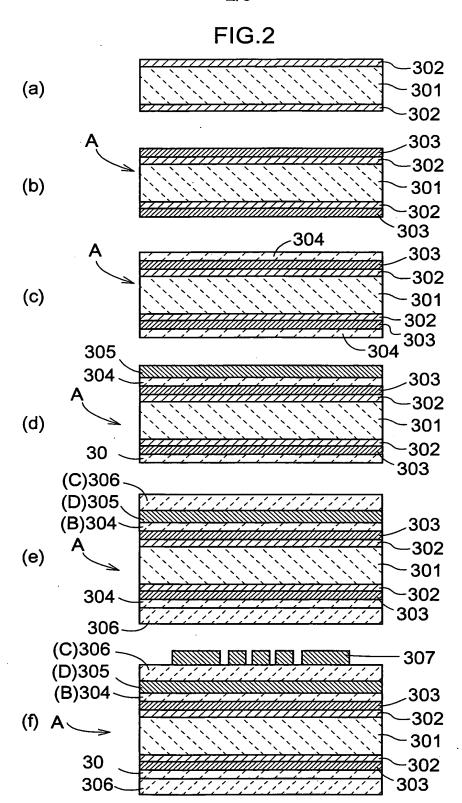
D: spacer 304: membrane, or polycrystal silicon film

E: acoustic opening 305: sacrificial layer

F: void area 306: polycrystal silicon film

314: take-out electrode

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